

## Description

# ELECTROSTATIC DISCHARGE (ESD) PROTECTION MOS DEVICE AND ESD CIRCUITRY THEREOF

### BACKGROUND OF INVENTION

[0001] 1. Field of the Invention

[0002] The present invention relates to electrostatic discharge (ESD) protection of circuitry. More particularly, the present invention relates to ESD protection NMOS devices with enhanced triggering property and improved ESD robustness. According to one preferred embodiment of the present invention, an improved ESD protection NMOS device possessing a trigger voltage of about 43 volts and a second breakdown current ( $I_{t2}$ ) of up to 2300mA (measured by the transmission line pulse generator) is obtained.

[0003] 2. Description of the Prior Art

[0004] Electro-static discharge (ESD) is a significant problem in integrated circuit design, especially for devices with high

pin counts and circuit speeds. ESD refers to the phenomena wherein a high-energy electrical discharge of current is produced at the input and/or output nodes of an integrated circuit (IC) device as a consequence of static charge build-up on the IC package. The static charge build up can result from handling of the IC device by a human body or from handling by IC device manufacturing equipments. It is known that the inadvertent presence of a sudden voltage spike in an integrated circuit can cause physical destruction of circuit features. For example, ESD-induced spikes can rupture the thin gate oxide of a field effect transistor (FET), or simply degrade the P-N junction of a semiconductor device, effectively destroying proper IC operation. A typical "gate oxide" in a MOS transistor will rupture when its dielectric strength is more than approximately  $10^7$  V/cm.

[0005] A variety of prior art ESD protection circuits are available. These prior art circuits can be based on Zener diodes, bipolar junction transistors, and/or field effect transistors (FETs). The circuits can be connected between input/output (I/O) pins and Vcc or Vss power supply pins. There have been many approaches to lower the ESD triggering voltages. One suggestion is found in U.S. Pat. No.

5,870,268 to Lin et al., which teaches generating, in response to an ESD event, a current spike that drives up the voltage of the P-well surrounding the ESD device. The higher P-well voltage lowers the trigger voltage of the ESD NMOS device. However, this approach requires additional circuitry.

[0006] It is often desired to have ESD devices built onto IC chips that can be reliably triggered at fairly low levels. As the sizes of the semiconductor MOS devices shrink to deep sub-micron scale, it becomes more difficult to control the "snapback" effect. Accordingly, there remains an unsatisfied need for more sensitive and faster responding ESD circuits. There is also a need for a simple IC structure that provides a low ESD trigger level reliably without extensive overhead circuitry and with an efficient use of IC space.

#### **SUMMARY OF INVENTION**

[0007] It is therefore the primary object of the present invention to provide a robust, sensitive and fast acting ESD protection device and ESD circuit thereof to solve the above-described problems.

[0008] It is another object of the present invention to provide an NMOS device having protection against electrostatic discharge, wherein the NMOS device has improved ESD per-

formance and robustness.

[0009] It is still another object of the present invention to provide an NMOS device having protection against electrostatic discharge, wherein the NMOS device has improved ESD performance and occupies relatively small chip surface area.

[0010] According to one preferred embodiment of this invention, an electrostatic discharge (ESD) protection MOS device is provided. The ESD protection MOS device includes a silicon substrate of first conductivity type; an epitaxial silicon layer of the first conductivity type grown on the silicon substrate; a first ion well of the first conductivity type disposed in the epitaxial silicon layer; a second ion well of the second conductivity type disposed in the epitaxial silicon layer, the second ion well encompassing the first ion well and laterally isolating the first ion well; a buried layer of the second conductivity type disposed at interface between the silicon substrate and the epitaxial silicon layer, wherein the buried layer borders the second ion well, thereby fully isolating the first ion well; a first isolation structure consisting of a gate insulating layer and a field oxide layer, wherein the first isolation structure is formed on the epitaxial silicon layer between the first and second

ion wells; a gate laid over the gate insulating layer and field oxide layer; a second isolation structure spaced apart from the first isolation structure, the second isolation structure being formed on the second ion well; a source doping region of the second conductivity type disposed in the first ion well between the gate insulating layer and the second isolation structure; and a drain doping region of the second conductivity type disposed in the second ion well between the field oxide layer and the second isolation structure.

[0011] From one aspect of this invention, an integrated circuit chip is provided. The integrated circuit chip includes at least one I/O pin, internal circuit, and an NMOS device having protection against electrostatic discharge. The NMOS device includes a P type silicon substrate; a P type epitaxial silicon layer grown on the silicon substrate; a P type first ion well disposed in the epitaxial silicon layer; a N type second ion well disposed in the epitaxial silicon layer, the second ion well encompassing the first ion well and laterally isolating the first ion well; a N type buried layer disposed underneath the first ion well, wherein the buried layer borders the second ion well, thereby fully isolating the first ion well from the silicon substrate; a

first isolation structure consisting of a gate insulating layer and a field oxide layer, wherein the first isolation structure is formed on the epitaxial silicon layer between the first and second ion wells; a gate laid over the gate insulating layer and field oxide layer; a second isolation structure spaced apart from the first isolation structure, wherein the second isolation structure is substantially formed on the second ion well; an N type source doping region disposed in the first ion well between the gate insulating layer and the second isolation structure; and an N type drain doping region disposed in the second ion well between the field oxide layer and the second isolation structure. The internal circuit of the integrated circuit chip comprises a high-voltage (HV) NMOS device having the same structure as the NMOS device except that the HV NMOS device does not have the N type buried layer.

[0012] From another aspect of this invention, an integrated circuit chip is provided. The integrated circuit chip includes at least one I/O pin, internal circuit, and an NMOS device having protection against electrostatic discharge. The NMOS device includes a P type silicon substrate; a P type epitaxial silicon layer grown on the silicon substrate; a P type first ion well disposed in the epitaxial silicon layer; a

N type second ion well disposed in the epitaxial silicon layer, the second ion well encompassing the first ion well and laterally isolating the first ion well; a N type buried layer disposed underneath the first ion well, wherein the buried layer borders the second ion well, thereby fully isolating the first ion well from the silicon substrate; a first isolation structure consisting of a gate insulating layer and a field oxide layer, wherein the first isolation structure is formed on the epitaxial silicon layer between the first and second ion wells; a gate laid over the gate insulating layer and field oxide layer; a second isolation structure spaced apart from the first isolation structure, wherein the second isolation structure is substantially formed on the second ion well; an N type source doping region disposed in the first ion well between the gate insulating layer and the second isolation structure; and an N type drain doping region disposed in the second ion well between the field oxide layer and the second isolation structure. The internal circuit of the integrated circuit chip comprises a high-voltage (HV) NMOS device having the same structure as the NMOS device except that the HV NMOS device has a buried diffusion layer with a doping concentration that is smaller than that of the N type

buried layer of the NMOS device.

[0013] Other objects, advantages and novel features of the invention will become more clearly and readily apparent from the following detailed description when taken in conjunction with the accompanying drawings.

#### **BRIEF DESCRIPTION OF DRAWINGS**

[0014] The accompanying drawings are included to provide a further understanding of the invention, and are incorporated in and constitute a part of this specification. The drawings illustrate embodiments of the invention and, together with the description, serve to explain the principles of the invention. In the drawings:

[0015] FIG. 1 is a schematic diagram showing ESD protection circuit for IC input pads and internal circuit of an IC chip;

[0016] FIG.2 is an enlarged plan view of the layout of the ESD protection NMOS device in accordance with the preferred embodiment of this invention; and

[0017] FIG.3 is a schematic cross-sectional diagram showing the ESD protection NMOS device along line I-I of FIG.2.

#### **DETAILED DESCRIPTION**

[0018] FIG. 1 shows a schematic diagram of an ESD protection circuit for IC input pads. The on-chip ESD protection cir-



cuit is built in IC chips to protect the devices and circuits against ESD damage. An input/output pad 11 is provided for interface with the internal circuit 13 of an IC chip. A PMOS 15 and an NMOS 17 are disposed between the input/output pad 11 and the internal circuit 13. According to one embodiment, the PMOS 15 and NMOS 17 devices are configured with their gates coupled to their respective sources. In general, for input pad protection, the junction breakdown voltages of the NMOS 17 and PMOS 15 should be smaller than the gate oxide breakdown voltage.

[0019] Referring to FIG.2 and FIG.3, wherein FIG.2 is an enlarged plan view of the layout of the NMOS device 17 in accordance with the preferred embodiment of this invention; FIG.3 is a schematic cross-sectional diagram showing the NMOS device 17 along line I-I of FIG.2. According to the preferred embodiment of this invention, the NMOS device 17 is a high-voltage NMOS device that is fabricated fully compatible with standard 40V high-voltage semiconductor CMOS processes. The NMOS device 17 is disposed between I/O pins and internal circuit of an integrated circuit chip to provided on-chip ESD protection. The present invention is especially suitable for ESD protection on an output buffer of integrated circuits.

[0020] As shown in FIG.2 and FIG.3, the NMOS device 17 is fabricated on an epitaxial silicon layer 14 that is grown on a silicon substrate 12 using methods known in the art. The NMOS device 17 comprises a polysilicon gate 20 laid over an insulating layer 18 and a high-voltage gate-insulating layer (typically silicon oxide) 19. The insulating layer 18 is formed by conventional field oxide process known in the art. The high-voltage gate-insulating layer 19 has a film thickness that is the same as that of a high-voltage MOS device fabricated in the internal circuit (not shown) of the integrated circuit chip. In accordance with the preferred embodiment of this invention, the aforesaid high-voltage MOS device is a 40V high-voltage device.

[0021] On one side of the gate 20, an  $N^+$  doping region 34 that is short-circuited with a  $P^+$  doping region 32 is provided in the epitaxial silicon layer 14. The  $N^+$  doping region 34 acts as a source terminal of the NMOS device 17. On the other side of the gate 20, an  $N^+$  doping region 36 is provided in the epitaxial silicon layer 14, which acts as a drain terminal of the NMOS device 17. The  $N^+$  doping region 36 is isolated from the gate 20 by the insulating layer 18. According to the preferred embodiment, the  $N^+$  doping region 34, the  $P^+$  doping region 32, and the gate

of the NMOS device 17 are coupled to  $V_{ss}$  or ground, but limited thereto.

[0022] The  $P^+$  doping region 32 and the  $N^+$  doping region 34 of the NMOS device 17 are formed in a P well 26. The  $N^+$  doping region 36 of the NMOS device 17 is formed in an annular N well 22 that encompasses the P well 26 and laterally isolates the P well 26. Both the N well 22 and the P well 26 are formed in the epitaxial silicon layer 14. An  $N^+$  buried layer (NBL) 24 is disposed under the P well 26. The NBL 24 borders the annular N well 22 and hence fully isolates the P well 26 from the silicon substrate 12.

[0023] According to the claimed invention, the NBL 24 is formed by ion implanting N type ion species such as phosphorus, arsenic or antimony into the silicon substrate 12 at implant dose that is greater than a specific value, followed by conventional epitaxial growing process and drive-in process. Accordingly, the NBL 24 is located at the interface between the silicon substrate 12 and the epitaxial silicon layer 14, as specifically indicated by the dash line in FIG.3.

[0024] According to the preferred embodiment of this invention, the NBL 24 is formed by ion implanting antimony (Sb) into said silicon substrate at an implant dose of at least  $1E15$

atoms/cm<sup>2</sup> and at an implant energy of about 80KeV. Preferably, the NBL 24 is formed by ion implanting anti-mony into said silicon substrate at an implant dose of about 2E15 atoms/cm<sup>2</sup> and at implant energy of about 80KeV. Under such condition (Sb; dose: 2E15 atoms/cm<sup>2</sup>; energy: 80KeV), a significant improvement of the second breakdown current (It2) of the NMOS device 17 is obtained. According to the experimental data measured by a Transmission Line Pulse Generator (TLPG), a second breakdown current (It2) of about 2300mA is achieved. It is surprisingly found that the additional implant of the NBL with controlled doping doses and energies can improve the ESD robustness of the NMOS device 17.

[0025] The present invention features the NBL 24 that is formed under controlled implant dose and energy conditions, and the annular N well 22, which in combination fully isolates the P well 26 that functions as a terminal of a parasitic bipolar junction transistor. It is believed that turn-on property of the parasitic bipolar junction transistor is further enhanced by tuning the conditions (dose and/or energy) related to the formation of the NBL 24. The trigger voltage of the NMOS device 17 is reduced. It is advantageous to use the present invention because the NMOS de-

vice 17 occupies relatively smaller chip surface area. According to the preferred embodiment, the NMOS device has a channel width to length ratio of about 20/3 ( $W/L=20/3$ ). The NMOS device 17 presents enhanced ESD performance and high ESD efficiency at small device area.

[0026] As shown in FIG.2 and FIG.3, a field oxide layer 16 is formed on the epitaxial silicon layer 14. The field oxide layer 16, which is spaced apart from the insulating layer 18, is approximately formed over the annular N well 22. The  $P^+$  doping region 32 and the  $N^+$  doping region 34 are formed between the field oxide layer 16 and the gate 20. The  $N^+$  doping region 36 is formed between the field oxide layer 16 and the insulating layer 18. The NMOS device 17 further comprises a field P well 28 implant through the field oxide layer 16 into the epitaxial silicon layer 14. Further, as shown in FIG.2, a guard ring structure 29 is provided. The guard ring structure 29 surrounds the NMOS device 17 and comprises a guard ring N well (not shown) adjacent to the field P well 28. According to the preferred embodiment, the guard ring structure 29 further comprises the aforesaid NBL directly underneath the guard ring N well.

[0027] As shown in FIG.3, a dielectric layer 42 is deposited over

the epitaxial silicon layer 14 and over the field oxide layer 16, insulating layer 18 and gate 20. Metal interconnection lines 56 and 58 are formed on the dielectric layer 42. The metal interconnection line 56 is electrically connected to the P<sup>+</sup> doping region 32 and N<sup>+</sup> doping region 34 via butting contact 52. According to the preferred embodiment, the P<sup>+</sup> doping region 32 and N<sup>+</sup> doping region 34 are coupled to the same voltage level such as V<sub>SS</sub>. The metal interconnection line 58 is electrically connected to the N<sup>+</sup> doping region 36 via contact 54. According to the preferred embodiment, the N<sup>+</sup> doping region 36 is coupled to the I/O pin and internal circuit. Briefly referring back to Fig.1, the gate 20 is coupled to the N<sup>+</sup> doping region 34.

[0028] To sum up, the NMOS device 17 of this invention is fabricated by using the same high-voltage processes that are used to fabricate high-voltage (HV) NMOS devices within the internal circuit of an integrated circuit chip, except that an additional ESD implant is carried out to form (or adjust) the NBL 24 under the NMOS device 17. Accordingly, except the NBL 24, the structures of the NMOS device 17 and the HV NMOS device within the internal circuit are the same. The NBL 24 that is formed under controlled

implant dose and energy conditions, and the annular N well 22, which in combination fully isolates the P well 26 that functions as a terminal of a parasitic bipolar junction transistor. The turn-on property of the parasitic bipolar junction transistor is enhanced by tuning the conditions (dose and/or energy) related to the formation of the NBL 24. The trigger voltage of the NMOS device 17 is reduced.

[0029] Furthermore, in some cases that the HV NMOS device within the internal circuit also has the N-type buried layer (NBL) design, the additional ESD implant is then used to increase the doping concentration of the NBL 24 under the NMOS device 17 that has protection against electrostatic discharge. It is noted that in such case, the ESD protection NMOS device 17 has a NBL 24 with a doping concentration that is higher than the doping concentration of the NBL of the HV NMOS device within the internal circuit.

[0030] Those skilled in the art will readily observe that numerous modification and alterations of the invention may be made while retaining the teachings of the invention. Accordingly, the above disclosure should be construed as limited only by the metes and bounds of the appended claims.